FORM PTO-1449

LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

(use several sheets if necessary)

SERIAL NO.

10/667,707

9905/35

FILING DATE
September 22, 2003

1765

APPLICANT(S): Moriceau et al.

REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE NAME		CLASS/ SUBCLASS	FILING DATE
SA	C1	4,254,590	3/10/1981	Eisele et al.	1	
1	C2	5,300,788	4/5/1994	Fan et al.		
	C3	5,400,458	3/28/1995	Rambosek		
	C4	5,811,348	9/22/1998	Matushita et al.	1.	
	C5	5,877,070	3/2/1999	Goesele et al.		
	C6	5,909,627	6/1/1999	Egloff		
	C7	5,953,622	9/14/1999	Lée et al.		· ·
	C8	5,994,207	11/30/1999	Henley et al.		
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	C10	6,054,370	4/25/2000	Doyle		
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	C12	6,146,979	11/14/2000	Henley et al.		
	C13	6,150,239	11/21/2000	Goesele et al.		
	C14	6,225,192	5/1/2001	Aspar et al.		
	C15	6,271,101	8/7/2001	Fukunaga		
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	C20	6,362,077	3/26/2002	Aspar et al.		-
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	C30	2003/0199105	10/23/2003	Kub et al.		
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EXAMINER		DATE CONSIDERED	
	/Shamim Ahmed/ (12/27/2006)		12/27/2006

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(use several sheets if necessary)	APPLICANT(S): Moriceau et al.	

EXAMINER INITIAL		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
SA	C35	EP 0 293 049 B1	9/29/1993	Europe		
	C36	EP 0 410 679 A1	1/30/1991	Europe		
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	C47	FR 2 748 850 A1	11/21/1997	France		Abstract
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	C50	FR 2 767 416 A1	2/19/1999	France		Abstract
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	C55	FR 2 797 347 A1	2/9/2001	France		Abstract
	C56	FR 2 809 867 A1	12/7/2001	France		Abstract
	C57	FR 2 847 075 A1	5/14/2004	France		Abstract
	C58	JP 62265717	11/18/1987	Japan		Abstract
	C59	JP 01004013	09/01/1989	Japan		Abstract
	C60	JP 7302889	11/14/1995	Japan		Abstract
	C61	JP 11045862	2/16/1999	Japan		Abstract
	C62	JP 11074208	3/16/1999	Japan		Abstract
	C63	JP 11087668	3/30/1999	Japan		Abstract
	C64	JP 11233449	8/27/1999	Japan		Abstract
	C65	WO 99/08316 A1	2/18/1999	WIPO		Abstract
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1/	C71	WO 02/47156 A1	6/13/2002	WIPO	1	Abstract
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INITIAL NUMBE		DOCUMENT NUMBER Number-Kind Code (if known)	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
	C74	WO 2004/044976	5/27/2004	WIPO		Abstract

EXAMINER							
INITIAL		OTHER ART – NON PATENT LITERATURE DOCUMENTS					
	(include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial,						
	symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.						
SA	C75	Agarwal et al "Efficient production of Silicon-on-insulator films by co-implatation of HE* with H*", Applied Physics Letter, American Institute of Physics, Vol. 72, No. 9, March 1998, pp. 1086-1088					
	C76	Bruel et al., [Vol. 99-1] Meeting Abstract No. 333, "Single-crystal semiconductor layer delamination and transfer through hydrogen implantation," <i>The 195th Metting of The Electrochemical Society</i> , May 2-6, 1999, Seattle, Washington					
	C77	Camperi-Ginestet et al., "Alignable Epitaxial Liftoff of GaAs Materials with Selective Deposition Using Polyimide Diaphragms", <i>IEEE Transactions Photonics Technology Letters</i> , Vol. 3, No. 12, December 1991, pp. 1123-1126					
	C78	Cerofolini et al. "Ultradense Gas Bubbles in Hydrogen-or-Helium-Implanted (or Co-implanted) Silicon", <i>Materials Science and Engineering</i> , B71, 2000, pp. 196-202					
	C79	Demeester, et al., "Epitaxial Lift-off and its Applications", Semicond. Sci. Technol., Vol. 8, 1993, pp. 1124-1135					
	C80	DiCioccio et al., "III-V layer transfer onto silicon and applications", <i>Phys. Stat. Sol. (a)</i> , Vol. 202, No. 4., 2005, pp. 509-515/DOI 10.1002/pssa. 200460411					
	C81	Feijoo et al., "Prestressing of Bonded Wafers", Vol. 92-7 1992 pp. 230-238					
	C82	Feng et al., "Generalized Formula for Curvature Radius and Layer Stresses Caused by Thermal Strain in Semiconductor Multilayer Structures", <i>J. Appl. Phys.</i> , Vol. 54, No. 1, 1983, pp. 83-85					
	C83	Hamaguchi, et al., "Novel LSI/SOI Wafer Fabrication Using Device Layer Transfer Technique" <i>Proc. IEDM</i> , 1985, pp. 688-691					
	C84	Henttinen et al. "Mechanically induced Si Layer Transfer in Hydrogen-Implanted Si-Wafers", American Institute of Physics, Vol. 76, No. 17, April 2000, pp. 2370-2372					
	C85	Kucheyev et al., "Ion implantation into GaN", <i>Materials Science and Engineering</i> , 33, 2001, pp. 51-107					
	C86	Liu et al., "Ion implantation in GaN at liquid-nitrogen temperature: Structural characteristics and amorphization," <i>Physical Review B of The American Physical Society</i> , Vol. 57, No. 4, 1988, pp. 2530-2535					
	C87	Moriceau et al., [Vol. 99-1] Meeting Abstract No. 405, "A New Characterization Process Used to Qualify SOI Films," <i>The 195th Meeting of The Electrochemical Society</i> , May 2-6, 1999, Seattle, Washington.					
SA	C88	Pollentier et al., "Fabrication of High-Radiance LEDs by Epitaxial Lift-off" SPIE, Vol. 1361, 1990, pp. 1056-1062					

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EXAMINER INITIAL	sympo	OTHER ART – NON PATENT LITERATURE DOCUMENTS le name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, sium, catalog, etc.), date page(s), volume-Issue number(s), publisher, city and/or country where published.
SA .	C89	Suzuki et al., "High-Speed and Low Power n* -p* Double-Gate SOI CMOS", <i>IEICE Trans. Electron.</i> , Vol. E78-C, No. 4, April 1995, pp. 360-367
	C90	Timoshenko, S., "Analysis of Bi-Metal Thermostats", J.Opt. Soc. Am., 11, 1925, pp. 233-256
	C91	Wong et al., "Integration of GaN Thin Films with Dissimilar Substrate Materials by Pd-In Metal Bonding and Laser Lift-off", <i>Journal of Electronic Materials</i> , Vol. 28, No. 12, 1999, pp. 1409-1413
1	C92	Yun et al., "Fractional Implantation Area Effects on Patterned Ion-Cut Silicon Layer Transfer," Dept. of Electrical Eng. And Computer Sciences, University of California, Berkeley, CA 94720, USA, 1999 IEEE International SOI Conference, Oct. 1999, pg. 129-30
SA	C93	Yun et al., "Thermal and Mechanical Separations of Silicon Layers from Hydrogen Pattern- Implanted Wafers," Journal of Electronic Materials, Vol. No. 36, No. 8 2001

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